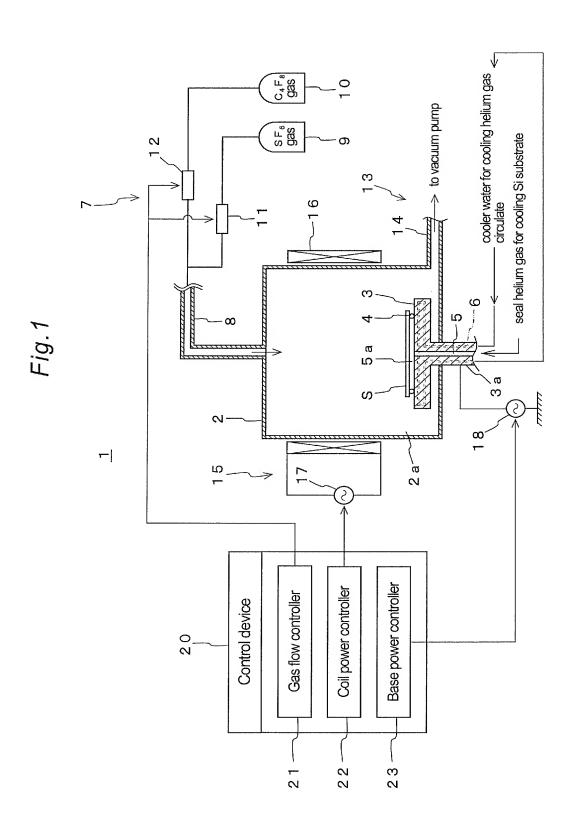
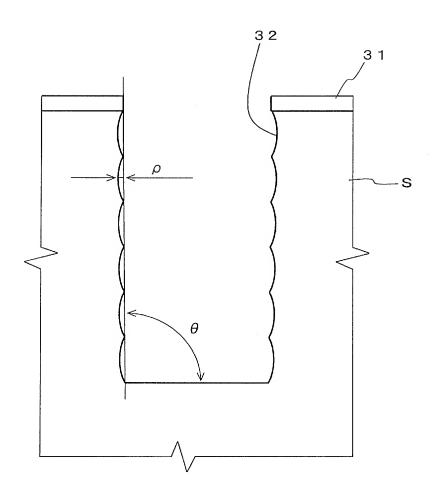
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Fig.3



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Fig.4

|                               | Embodiment | Comparative<br>Example |
|-------------------------------|------------|------------------------|
| Etching rate (µm/min)         | 3.7        | 3.4                    |
| Mask selection ratio          | 140        | 104                    |
| Unevenness $\rho$ (nm)        | 160        | 250                    |
| Hole sidewall angle (degrees) | 90.2       | 90.5                   |